

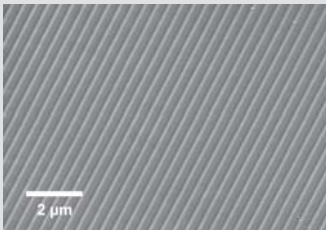
Laser Fabrication of Micro-Optics

Excimer laser micro machining

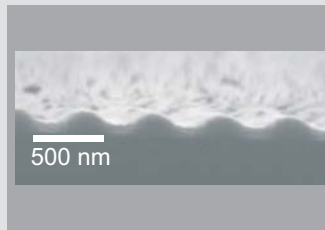
Laser induced material ablation enables processing of plastics, ceramics, glass, metals, and semi-conductors with high precision. UV excimer lasers facilitate micro machining with feature sizes in the sub micron range. Due to short pulse durations the thermal damage of the material is minimized. Fast and flexible processing using mask projection techniques open up numerous applications in micro-optics, micro-fluidics, and MOEMS. For the generation of optical structures on transparent materials, the application of deep UV and vacuum UV wavelengths is essential.

Gratings

Fused silica



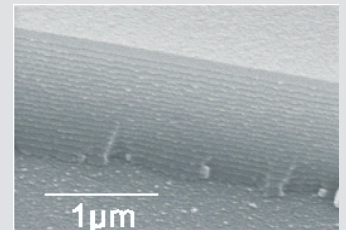
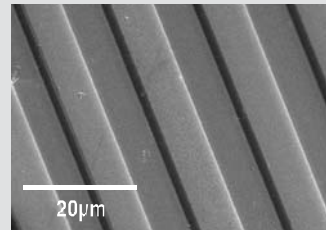
Ta₂O₅ waveguide



Gratings with periods of about 500 nm are made by projection of a master grating on fused silica (laser wavelength 193 nm) and on a Ta₂O₅ waveguide layer (femtosecond laser at 248 nm).

Dielectric masks

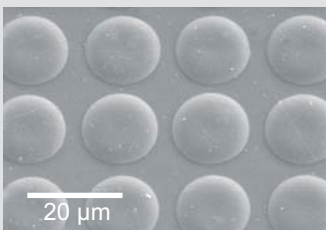
Al₂O₃/SiO₂ multilayer



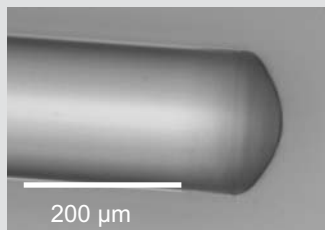
Dielectric masks fabricated by patterning a highly reflective multilayer stack (Al₂O₃/SiO₂) using 193 nm ablation. In the closed-up view of the edge (right), the multilayer structure becomes visible.

Micro lenses

PMMA



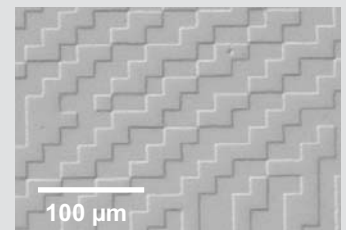
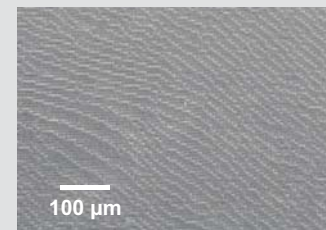
Fused silica fiber



Polymer micro lens array made by 308 nm -laser induced surface swelling (left). Micro-lens on the end face of a multi-mode silica fiber excised by F₂-laser ablation (157 nm) (right).

Diffraction phase elements

Fused silica



Four level diffraction phase element fabricated by F₂-laser ablation (157 nm) (left), and a binary element made by a special process allowing for the patterning of silica at 248 nm (right).



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